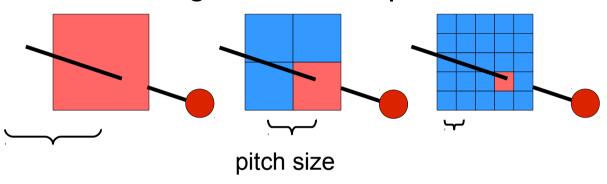


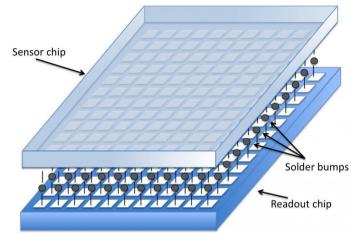
Concept of an enhanced later drift sensor

Manufacturing the bulk

How to archive high resolution?

Accurate guess: make pitch smaller



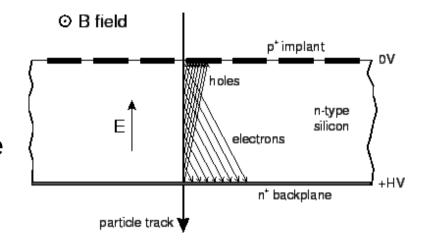


- → Increases number of readout channels
- → Potentially higher band width from detectors
- → Less space on-chip per channel
- → Higher power dissipation
- Miniaturisation has limits
 - → Size of bump bonds, wire bond pads, cross talk,
 - → Minimum of logic/processing on-chip
 - → Is there another solution?



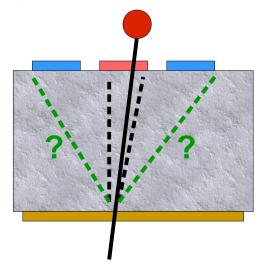
Charge coll. at perpendicular incident

- Enable charge sharing by
 - B-field and/or tilting of sensor
 - increases effective area collecting charge
 - increases material budget in beam



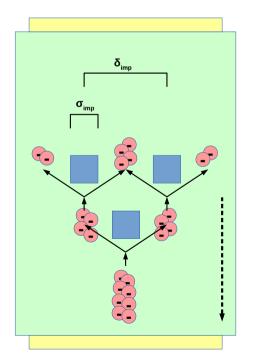
- No tilt + no magnetic field:
 - → Little to no charge sharing

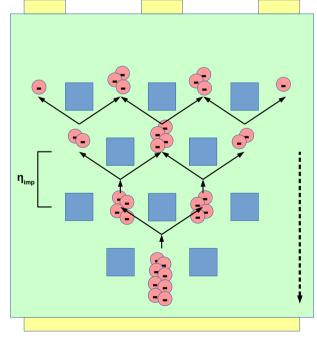
 How can charges be spread laterally, left and right?

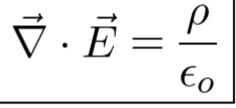


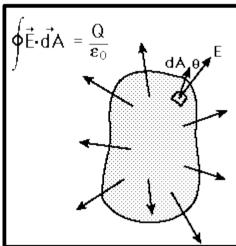
Manipulating the electric field

- Path of drifting charges follows the electric field lines
 - → Local doping changes the electric field locally
 - → Tailor electric field as needed!
- If approached head-on, repulsive areas split the charge cloud 50-50.
 - → Apply this layer-wise.









- → Achieve lateral enlargement of charge cloud independent of the incident position
- → Charge weighting enabled over the entire pitch length

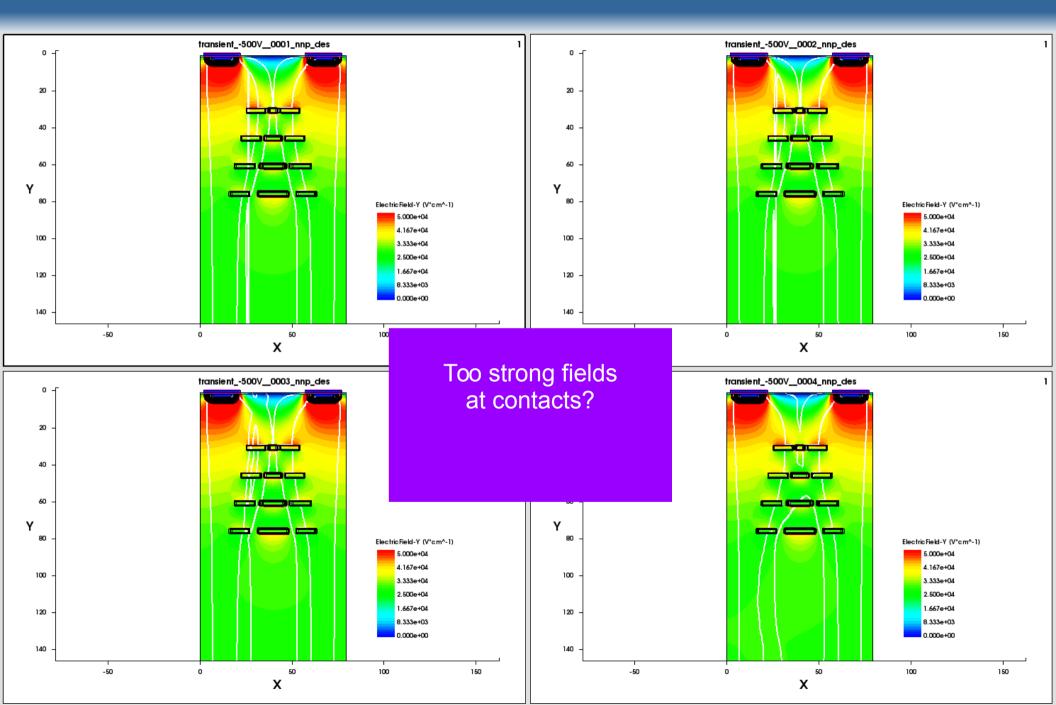
contacts

p-bulk

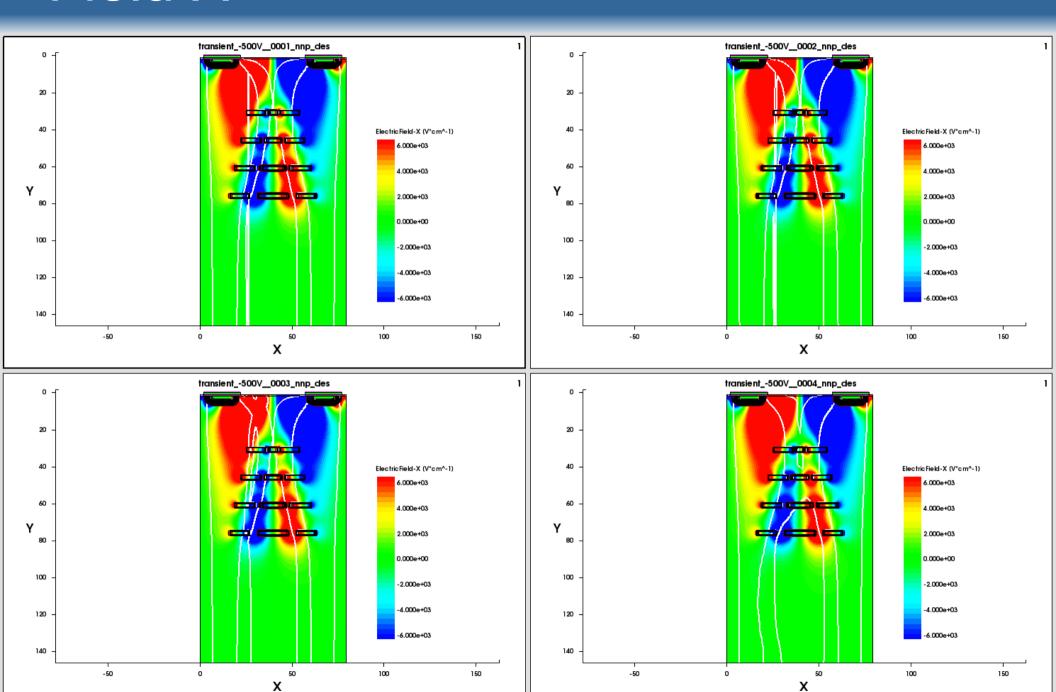
Elec. field

p⁺-implants

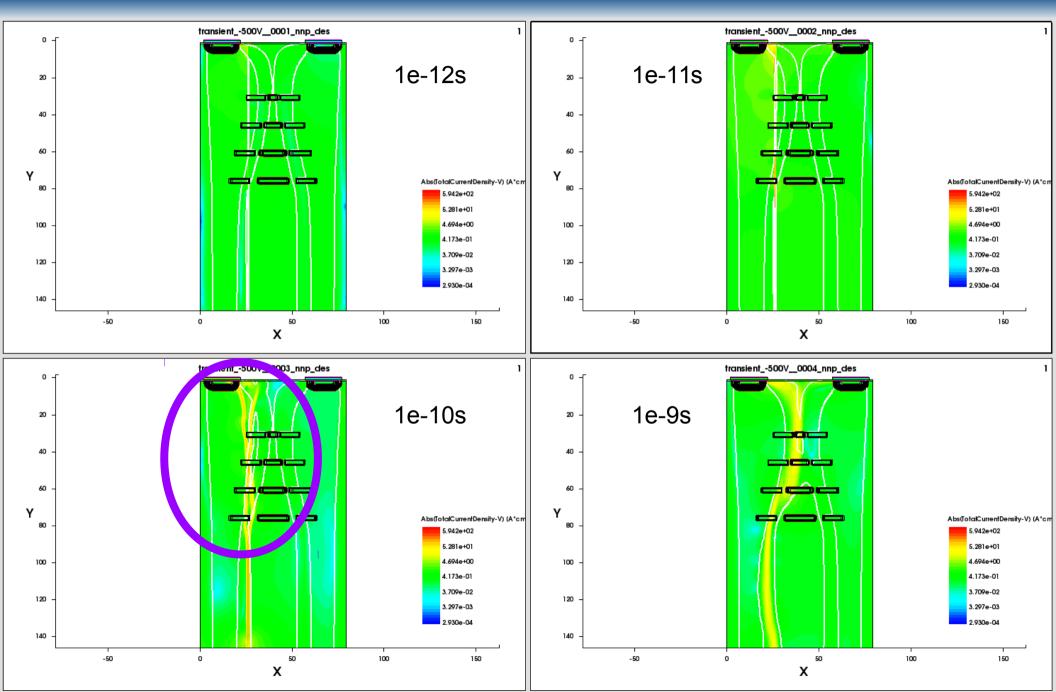
Field Y



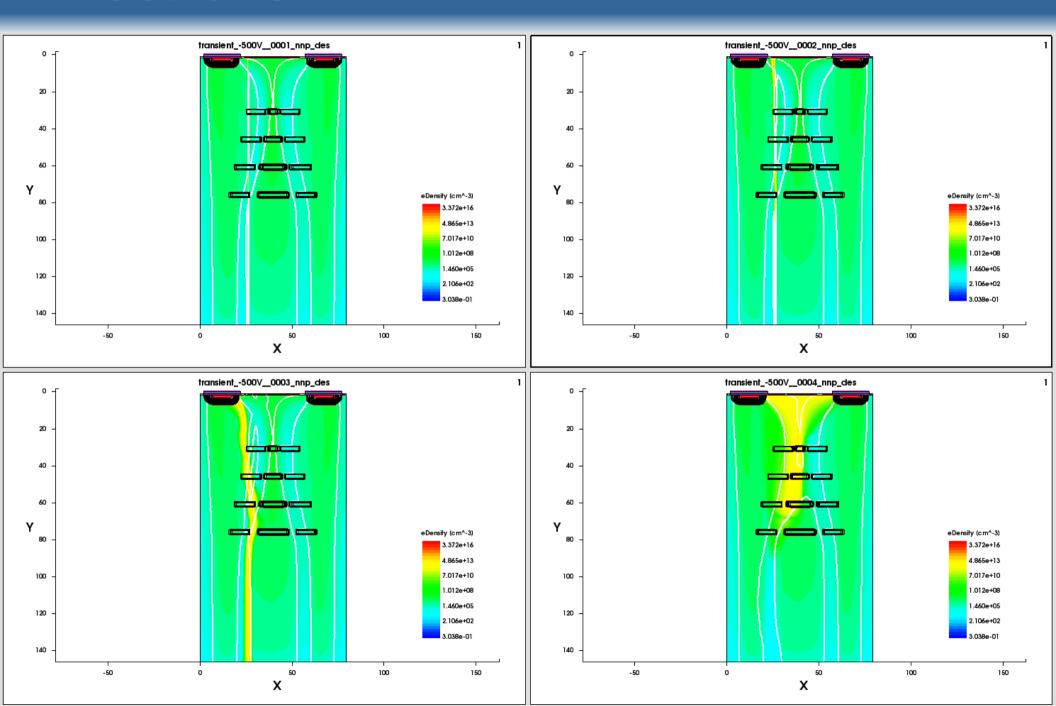
Field X



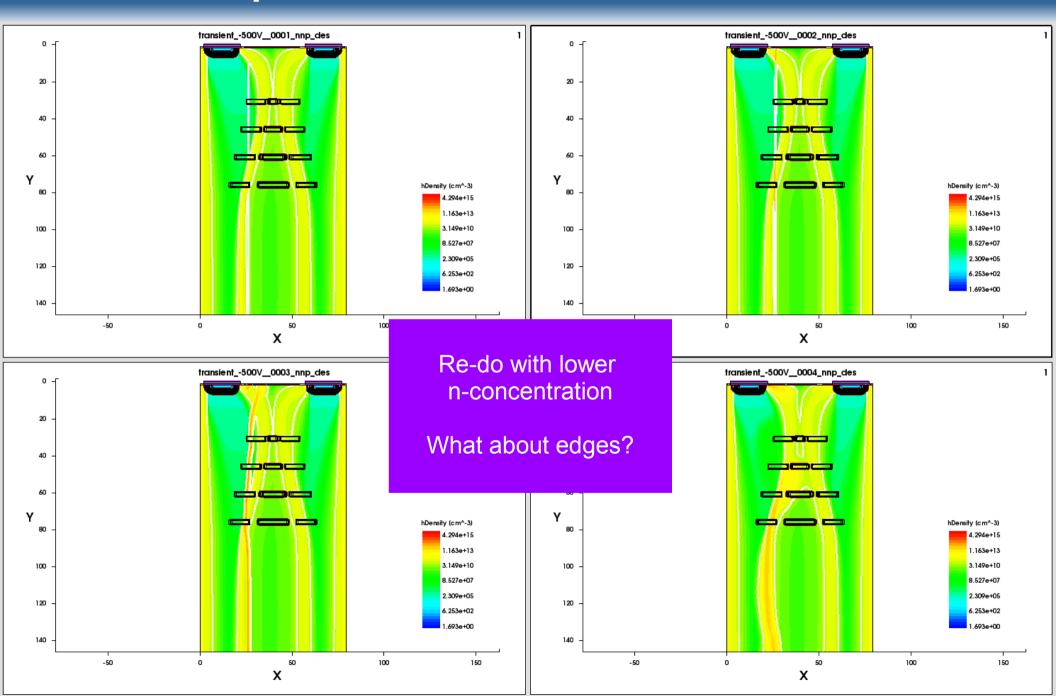
Absolute current



Electrons

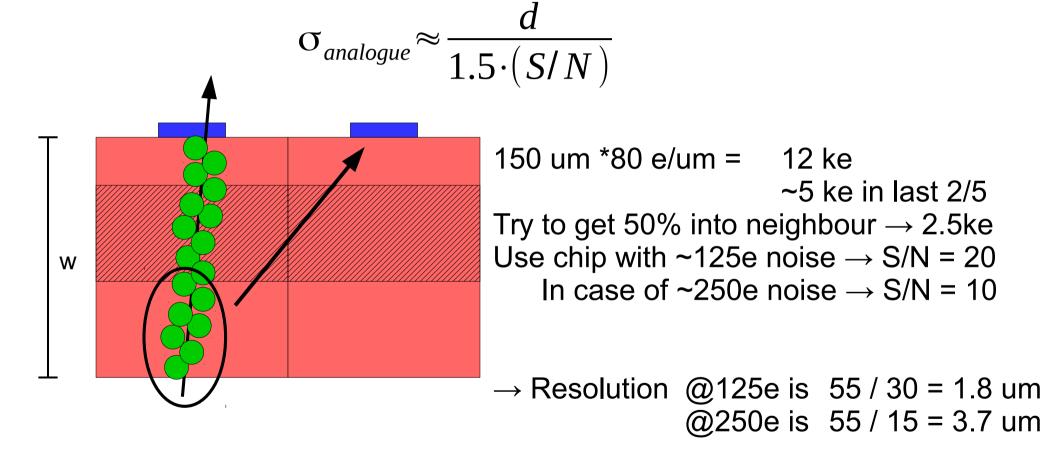


Holes - problematic



Pascalian Lateral Drift Detector II

Analogue resolution at 55 um pitch ("rule of thumb"):



Production

• Let's lave a look on the other PDF.

Pros and Cons

Pros

- Disentangle occupancy from resolution
- Higher resolution for same pitch size (clustersize 2)
- Higher resolution w/o B-field or tilted sensors
- Maintain fast signal (no coupling of read-out entities)

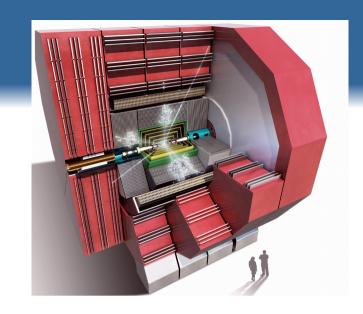
Cons:

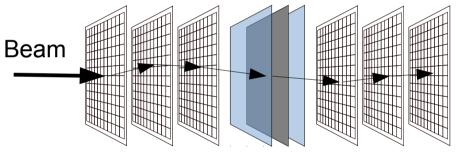
- Production will be "interesting" (no one tried this before)
- How well can one grow silicon on implanted silicon?
- Costly due to multilayer processes

Future applications

• (?) Clic / ILC

 Fast, high resolution beam telescopes:





• (?) Soft X-Ray CT of small objects with um resolution requirement



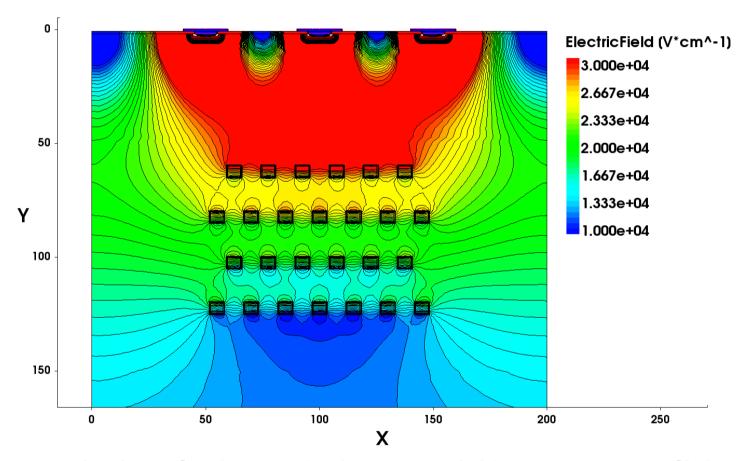
Conclusion

- Trying to break the small pitch dogma
- Charge sharing by lateral spread of charges
- Lateral spread enabled by charge guiding implants
- Simulations so far do not rule this idea out
- More simulations in the next months
- PIER grant for sensor production
- Patent submitted
- PhD student started with non-TCAD tool, now switches to TCAD

Back-up

TCAD Simulation

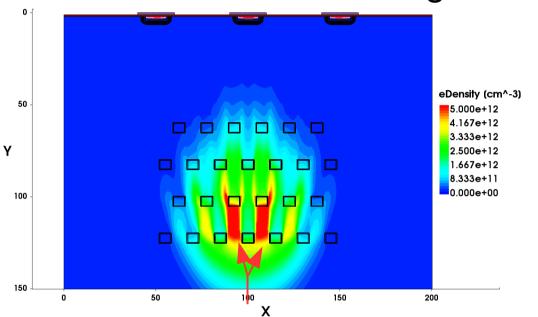
Simulation of E-field using TCAD tools:

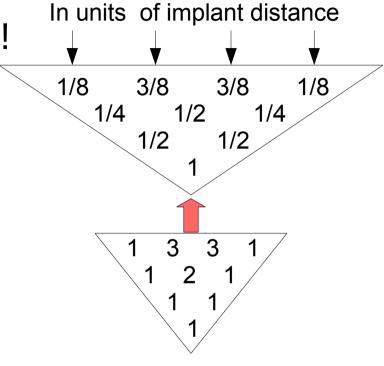


... and simulation of charge drift → next slide

Pascalian Lateral Drift Detector I

Lateral increase of charge cloud!





- 50-50 splitting as in normalised Pascal's triangle
- For 50 um pitch (bin. res. = 14.4 um),

what is achievable in terms of resolution?

Charge collection at low angle

Enable charge sharing by

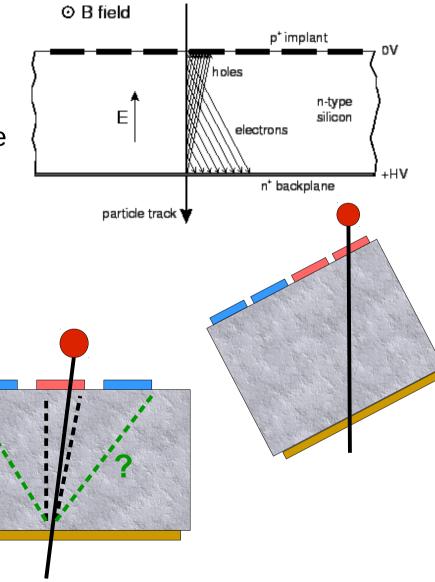
B-field and/or tilting of sensor

- increases effective area collecting charge
- increases material budget in beam

No tilt + no magnetic field:

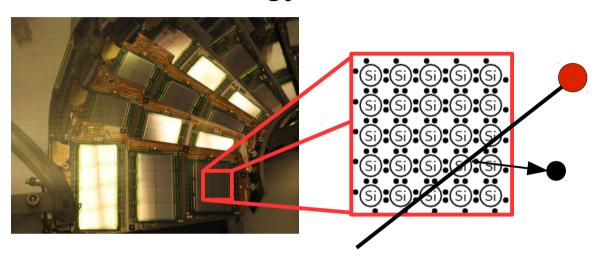
→ Little to no charge sharing

 How can charges be spread laterally, left and right?



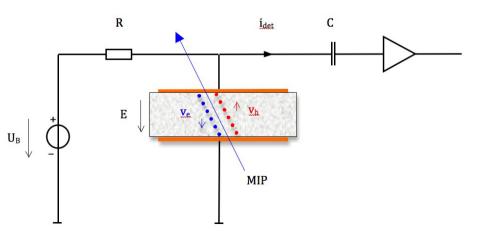
How to detect (charged) particles?

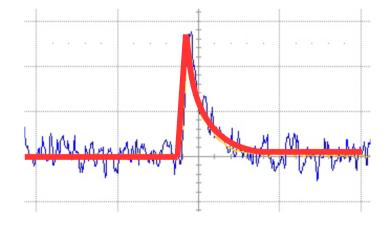
Detect the energy transferred to the traversed medium



Traversing particle creates free electrons and holes that are accelerated by an external electric field

Apply external electric field, amplify and read current



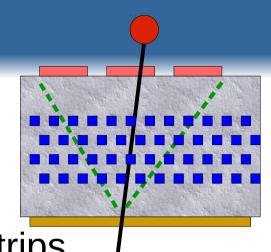


Challenges

Binomial with p = 0.5 tends towards
Gauss for high n

$$\rightarrow \sigma = \text{sqrt (npq)*}\delta_{\text{imp}} \approx 1*\delta_{\text{imp}}$$
.

Not enough charge on the neighbouring strips.

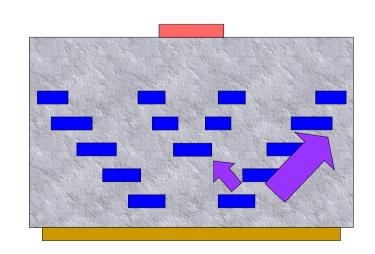


Solution?

 Tweak position of implants: "directional pLAD" sensor

$$\rightarrow$$
 p = 4/5 towards neighbour

$$\rightarrow Q_{nb} = (4/5)^6 = 0.26$$



Parameters in simulation

- Structure can be modified with respect to
 - Width, depth, concentration of implants
 - distance within/to next layer
 - position/shift to neighbouring layer
 - number of layers
 - possible defined by implantation

- ...

- Parameters need to be tuned to
 - choice of read-out: pixel or strip
 - its threshold and pitch